Multimedia Available: Applied Materials Shatters Metrology Roadblocks for 65-45nm Production with Applied VeritySEM System

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--(BUSINESS WIRE)--

Applied Materials Inc. (Nasdaq:AMAT) extends its leadership in CD-SEM(a) technology with the new high-throughput Applied VeritySEM(tm) Metrology system. Proprietary new SEM technology enables a remarkable less than 5 angstrom precision for tightly controlling ArF(a) resist structures, line edge roughness and feature shape in 65-45nm device structures. Multiple VeritySEM systems can be matched both internally and between fabs to within one nanometer.

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(a) CD-SEM: critical dimension -- scanning electron microscope
ArF: argon fluoride

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